

ABSTRACT OF THE DISCLOSURE

PLASMA CVD APPARATUS, METHOD FOR MANUFACTURING MAGNETIC
RECORDING MEDIUM AND METHOD FOR DEPOSITING FILM

To provide a plasma CVD apparatus capable of depositing
5 a film having good thickness uniformity. An aspect of the
present invention is a plasma CVD apparatus including a
chamber 102, a holding part that holds a substrate to be
deposited 1, a first direct-current power source 112
connected electrically with the holding part, a first anode
10 104a arranged on one side of the holding part, a first cathode
103a arranged on one side of the holding part, a second
direct-current power source 107a connected electrically with
the first anode, a first alternating-current power source
105a connected electrically with the first cathode, a gas
15 supply mechanism that supplies raw material gas to the inside
of the chamber, and a control part 130 that controls the first
direct-current power source so as to apply a first voltage
to the holding part in a pulse form of a cycle of not less
than 1/100 msec and not more than 1 msec and a DUTY cycle
20 of not less than 10% and not more than 90%.

(No drawing to be published)